

# Test Beam Characterisation of Passive CMOS Strip Sensors

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HELMHOLTZ



# Passive CMOS Technology

## The need for alternative silicon sensor designs

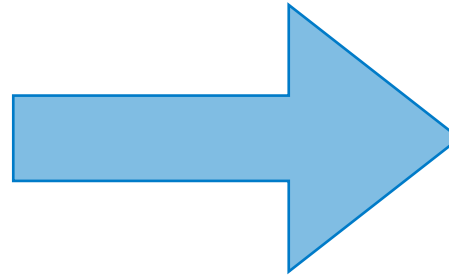
- Silicon sensors have become **indispensable** in high energy physics.

- They are...

... main tracking devices

... immense cost-driver

... only available from few foundries



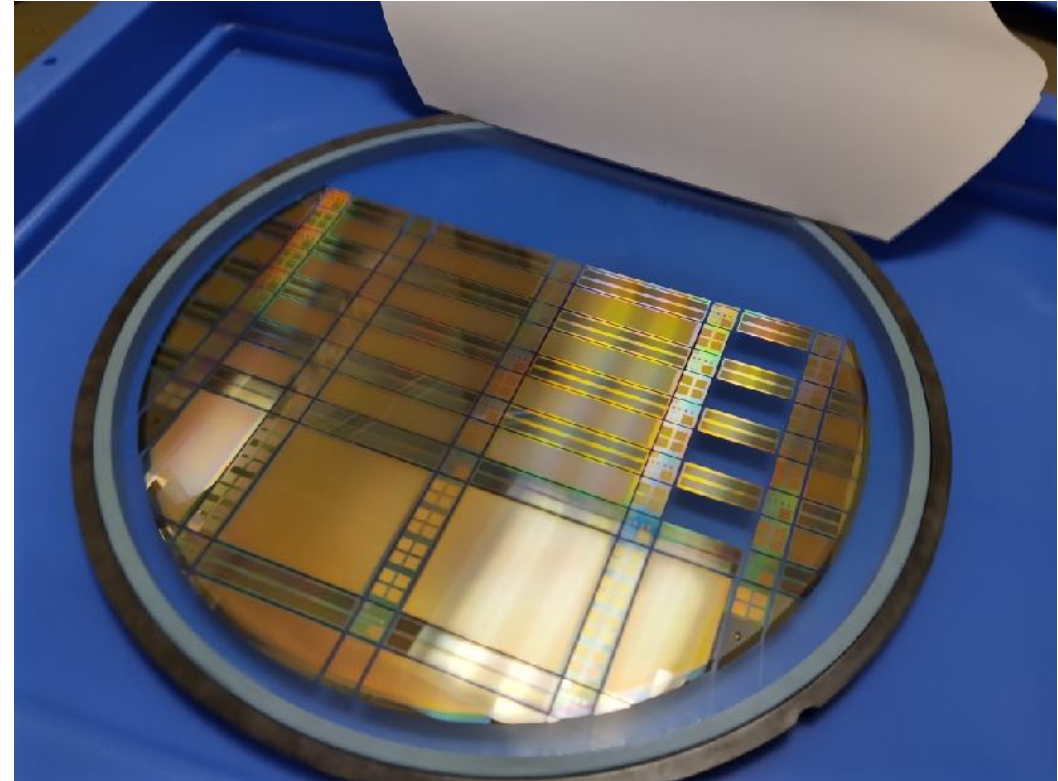
Alternative concepts ?

Alternative vendors ?

# Passive CMOS Technology

## A promising candidate

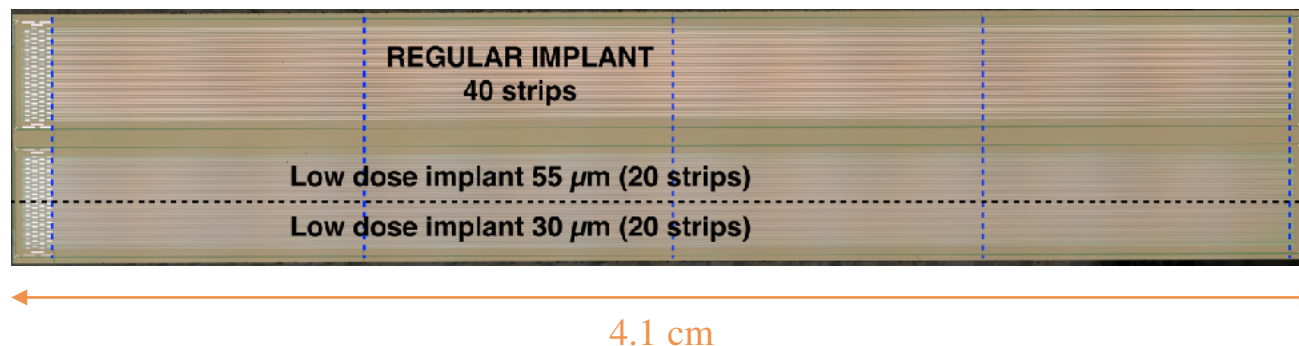
- CMOS imaging process
- Possible cost reduction
- Fast, large-scale production
- Wafer-scale industrial production
- Large vendor choice



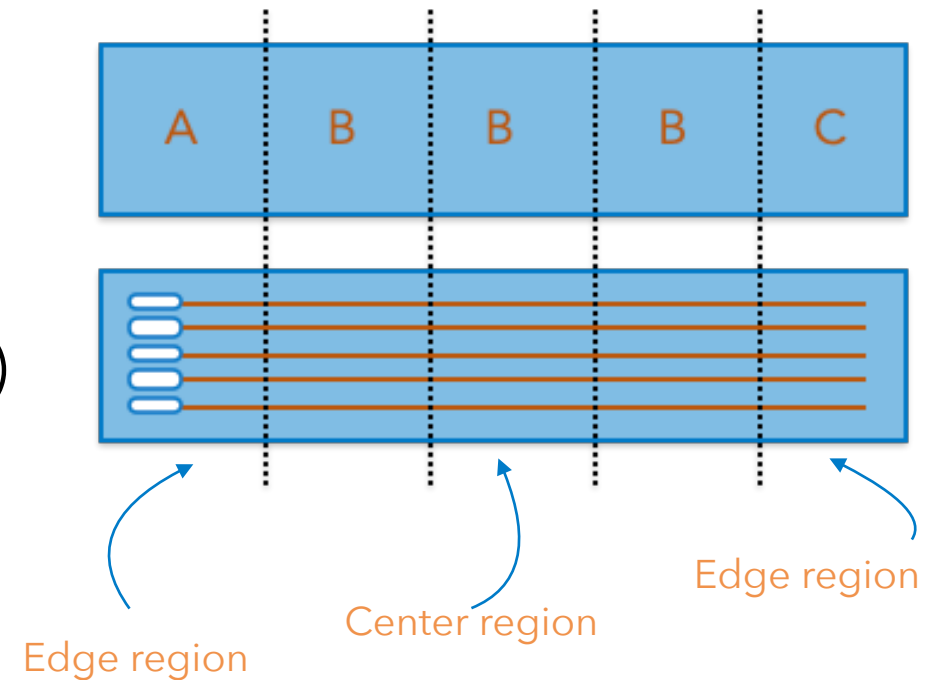
# Sensor Design

## Stitched strip sensors

- n-in-p sensor in **150 nm** LFoundry technology
- Float-Zone wafer with **3 – 5 k $\Omega$  · cm** resistivity
- $150 \pm 10$   $\mu\text{m}$  thickness, **75.5  $\mu\text{m}$**  strip pitch
- Connection of neighbouring reticles (**Stitching**)



Stitching is possible  
in both dimensions

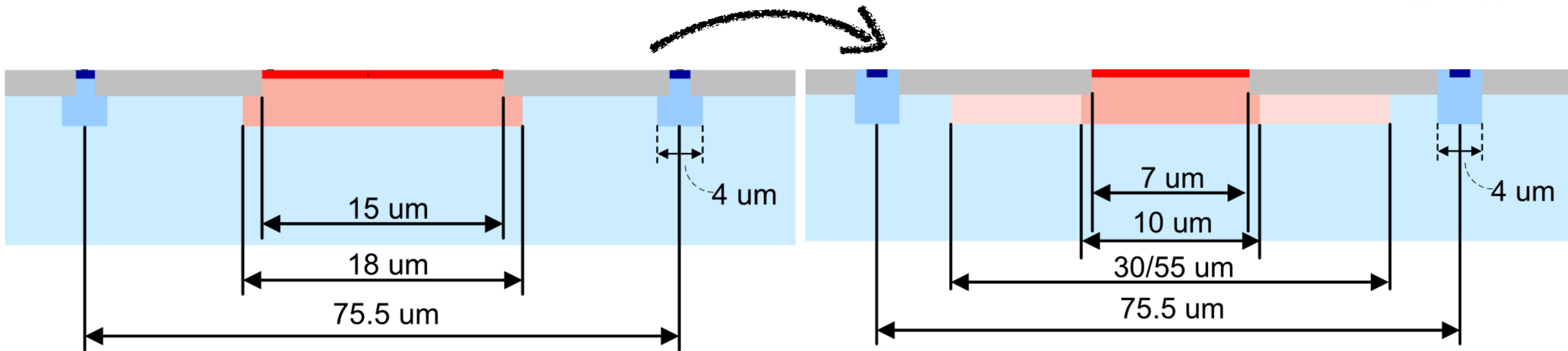


# Sensor Design

## Varying n-well characteristics

+ charge sharing  
- higher input capacitance

- Pwell
- Nwell
- P+
- N+
- Low-dose N



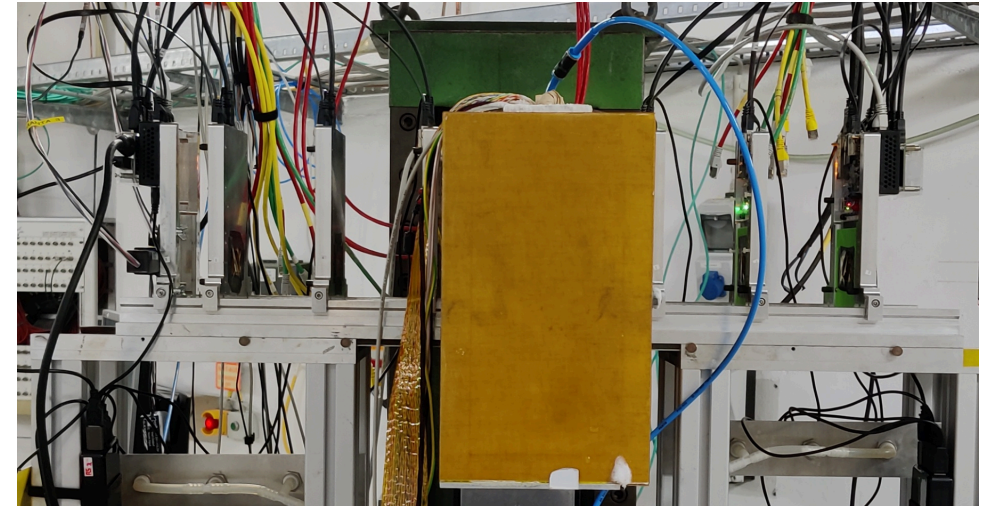
Regular implant strip design

Low Dose (LD) implant strip design

# Test Beam Setup

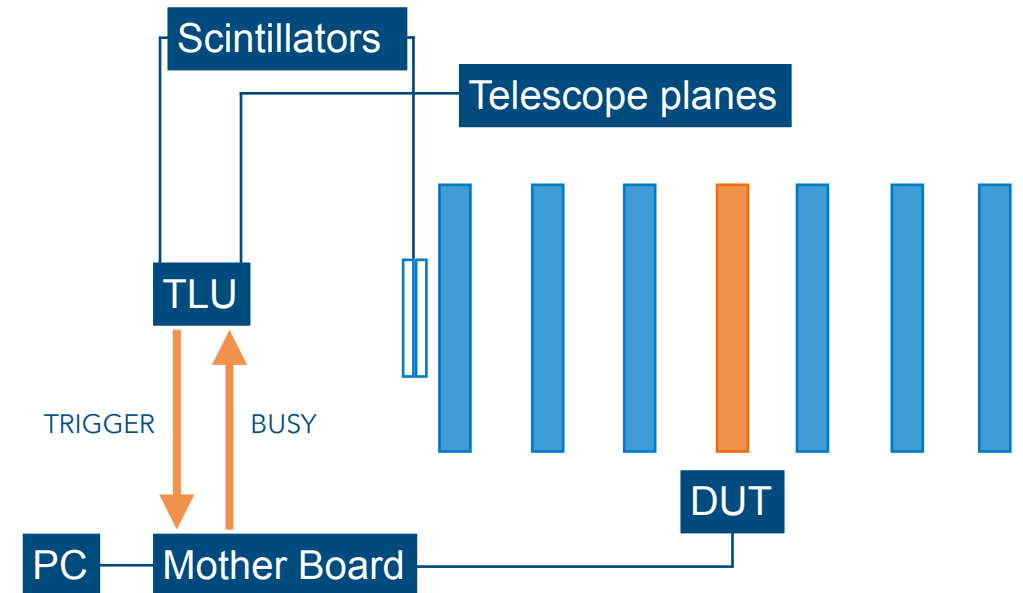
## Testing the sensor performance

- TB campaigns in Nov21, May22 at DESY-II
- **EUDET telescope** with 6 ALPIDE planes as reference
- $e^-$  beam energy: 3 GeV, 3.4 GeV
- Styrofoam **cold box**, cooling with dry ice



**NOV21:**  
Unirradiated,  
@100V bias, short

**MAY22:**  
Irradiation with reactor neutrons  
in Ljubljana  
3e14 @250V bias, short



J. Dreyling-Eschweiler et al., "The DESY II test beam facility", NIMA, Vol 922 (2019)


<https://doi.org/10.1016/j.nima.2018.11.133>

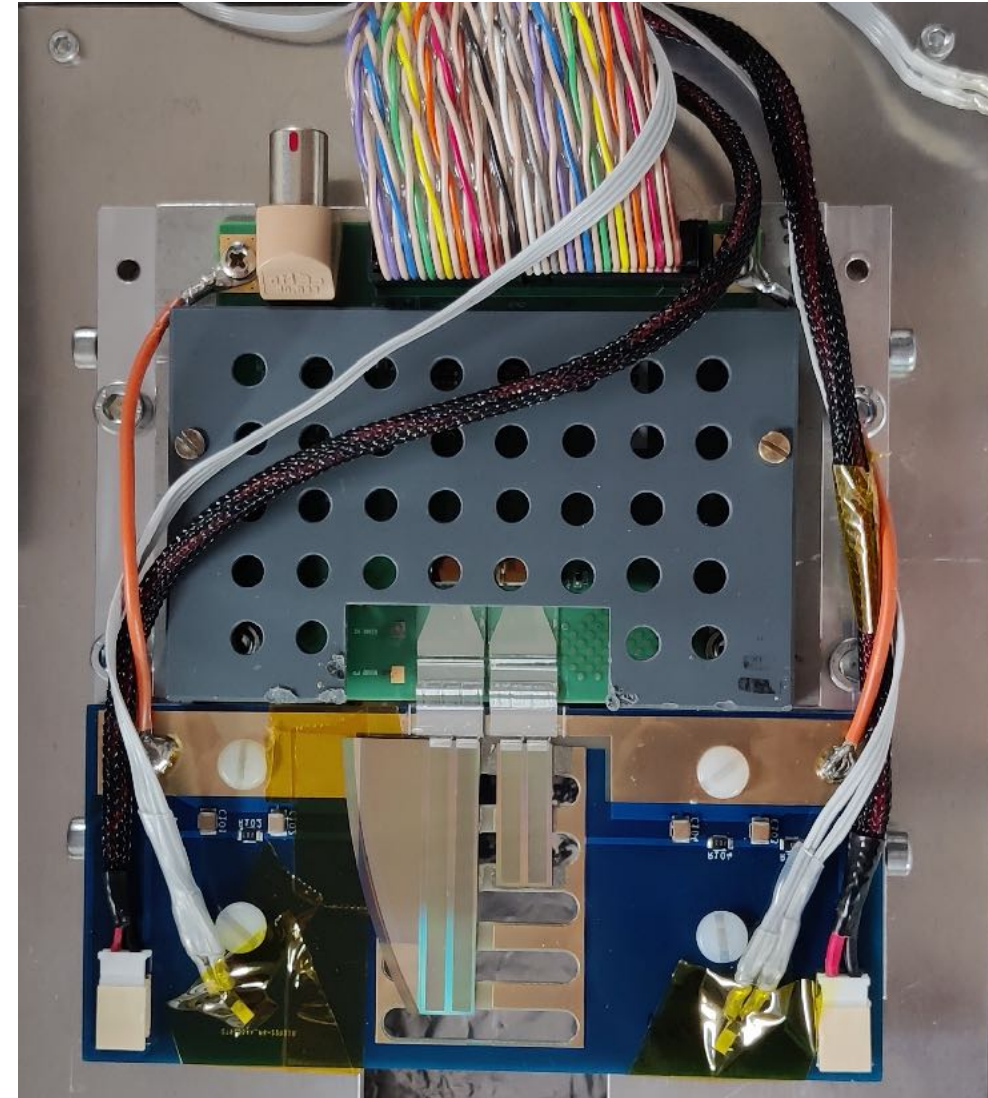
H. Jansen et al., "Performance of the EUDET-type beam telescopes", EPJ Techn Instrum 3, 7 (2016)

<https://doi.org/10.1140/epjti/s40485-016-0033-2>

# ALiBaVa Readout System

## ALiBaVa Daughterboard

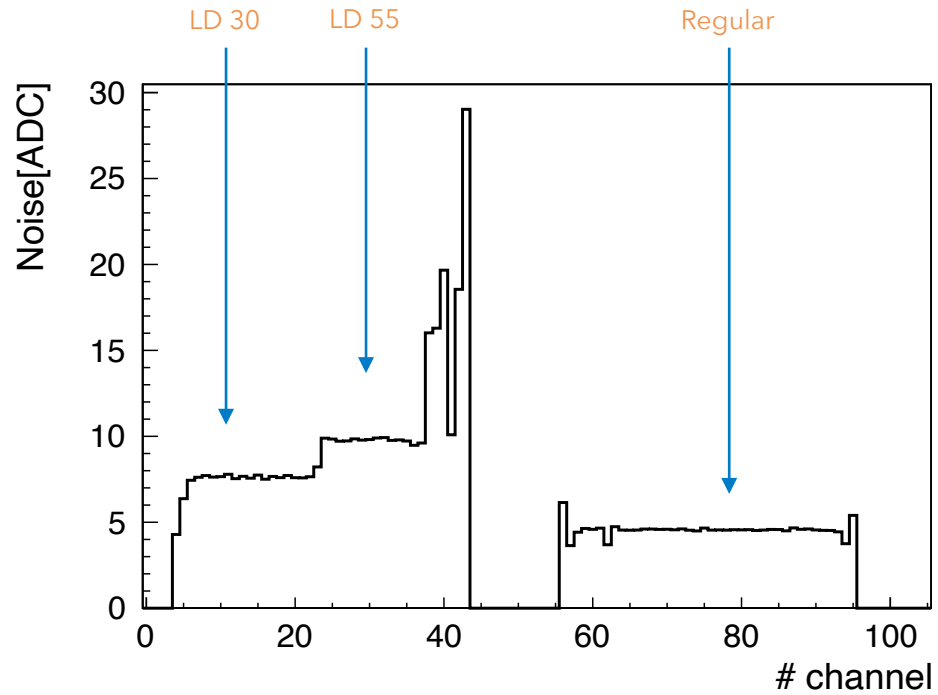
- ALiBaVa readout system for DUT data acquisition
- 128-channel Beetle Chip
- Reconstruction and Analysis with Corryvreckan 
- [EventLoaderALiBaVa] for DUT



D. Dannheim et al., "Corryvreckan: a modular 4D track reconstruction and analysis software for test beam data", J. Instr. 16 (2021) <https://doi.org/10.1088/1748-0221/16/03/P03008>  
R. Marco-Hernandez et al., "ALIBAVA: A portable readout system for silicon microstrip sensors", NIMA, Vol 623 (2010) <https://doi.org/10.1016/j.nima.2010.02.197>

# ALiBaVa Readout System

## EventLoaderALiBaVa

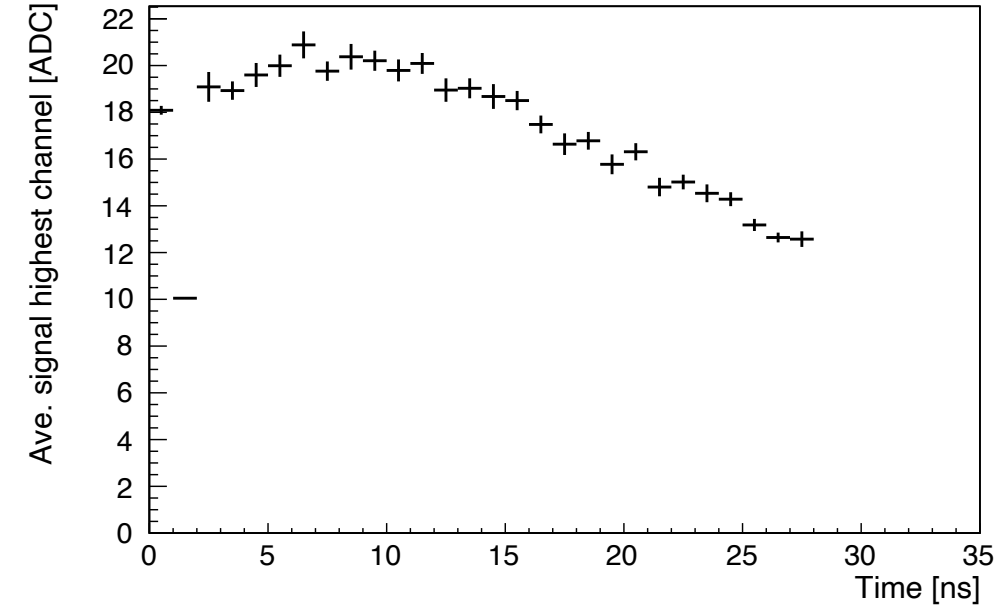


Sensor noise per beetle chip channel



2.1 cm

**NOV21:**  
Unirradiated,  
@100V bias, short



Average signal pulse waveform



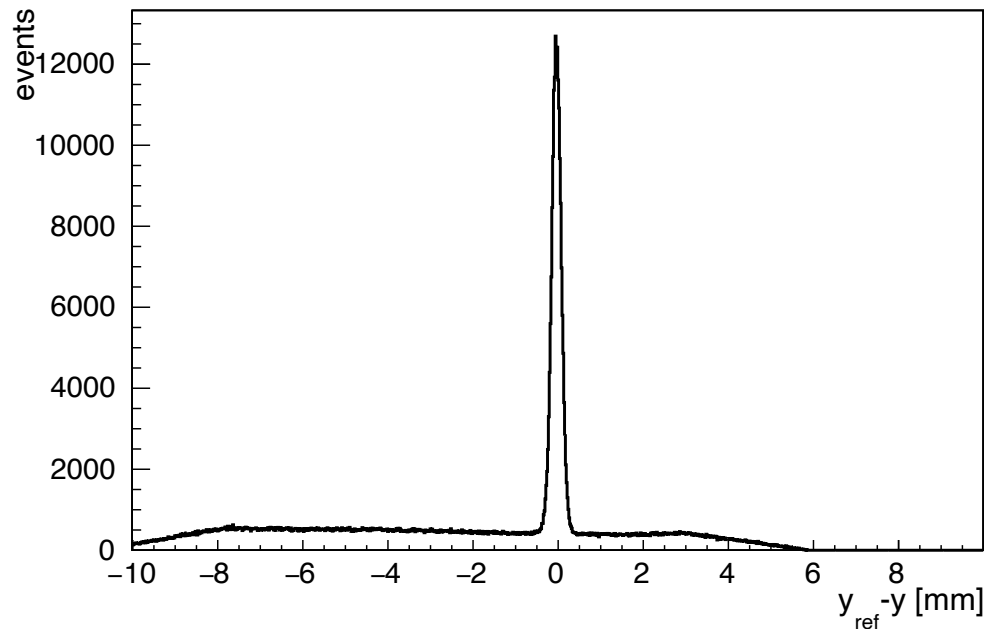
# Correlations

## Beam particle track rate

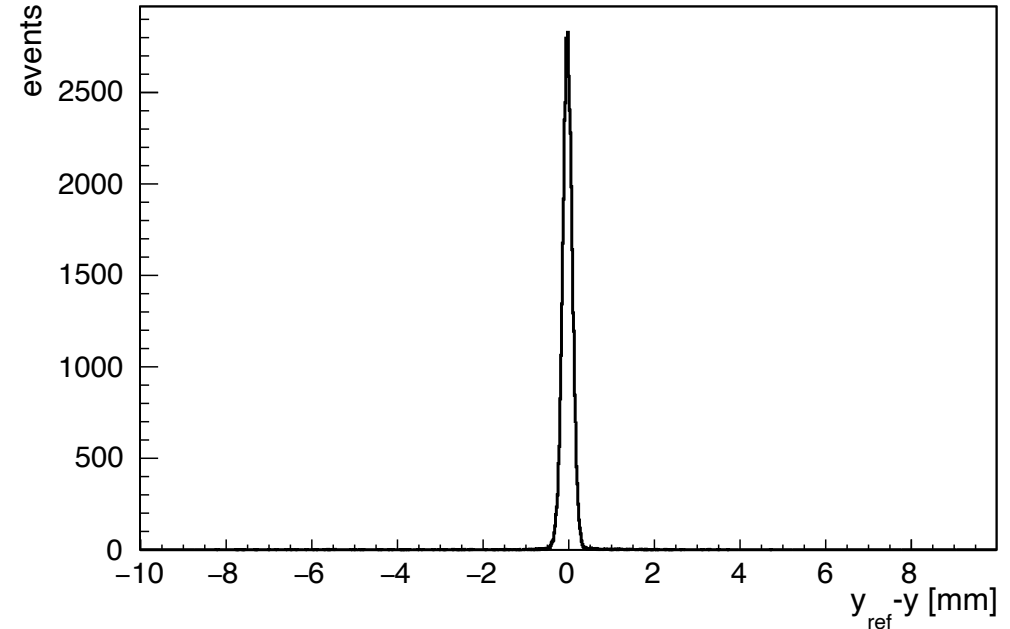
- High particle track rate in TB Nov 21 and May 22
- Issue: different integration times of DUT and telescope ( $\sim 75$  ns vs  $\sim 30$  us)
- [FilterEvents] module: restriction to one cluster per event

Additional timing plane  
in TB March 23

**NOV21:**  
Unirradiated,  
@100V bias, short



Correlation Y between telescope and DUT



Correlation Y between telescope and DUT (Filter)

# In-Strip Efficiency

Efficiency within the strip of an unirradiated sample

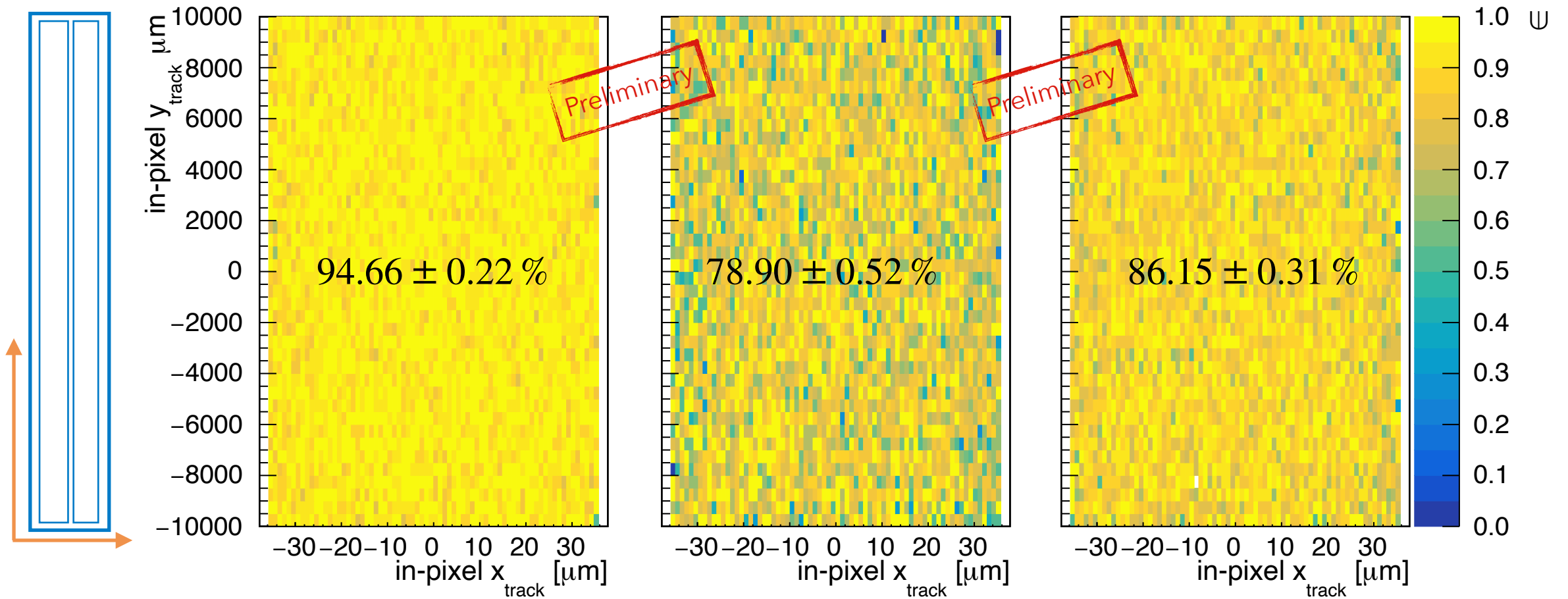
$$\epsilon_{reg} > \epsilon_{ld30} > \epsilon_{ld55}$$

NOV21:  
Unirradiated,  
@100V bias, short

Regular

LD 55

LD 30



# In-Strip Efficiency

Efficiency within the strip of an irradiated sample

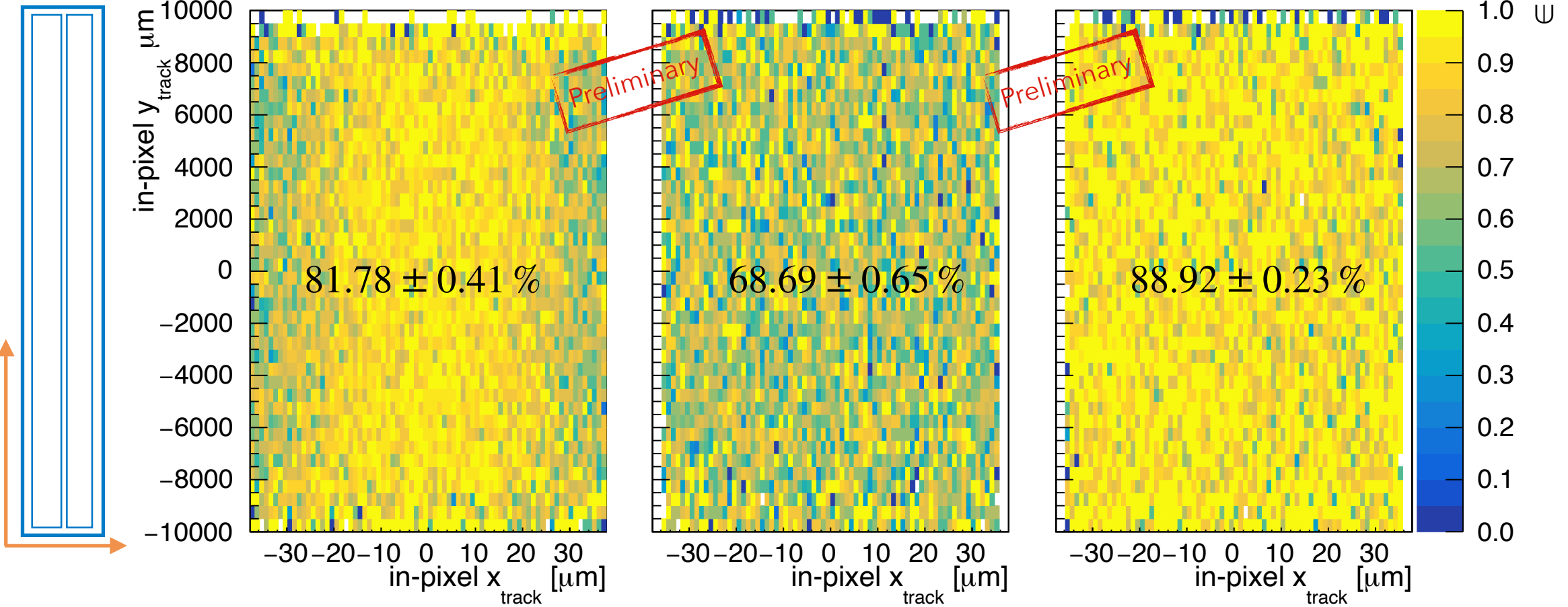
$$\epsilon_{ld30} > \epsilon_{reg} > \epsilon_{ld55}$$

MAY22:  
Irradiation with reactor neutrons  
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3e14 @250V bias, short

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LD 55

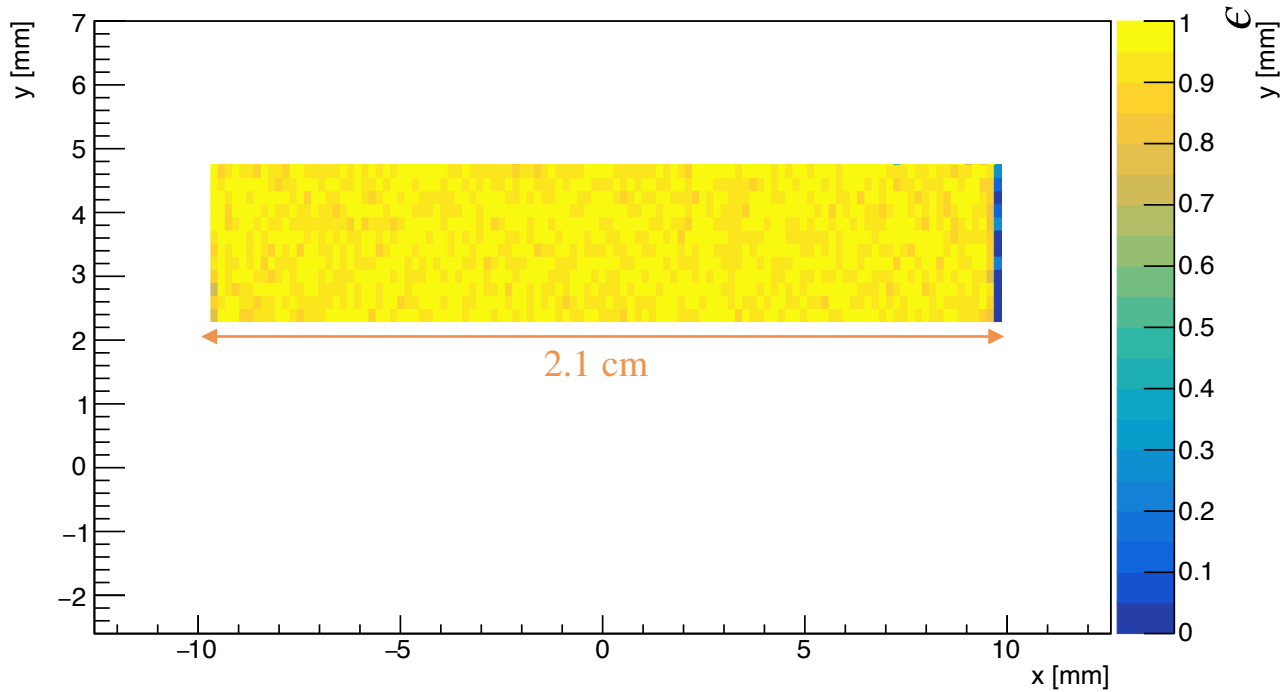
LD 30



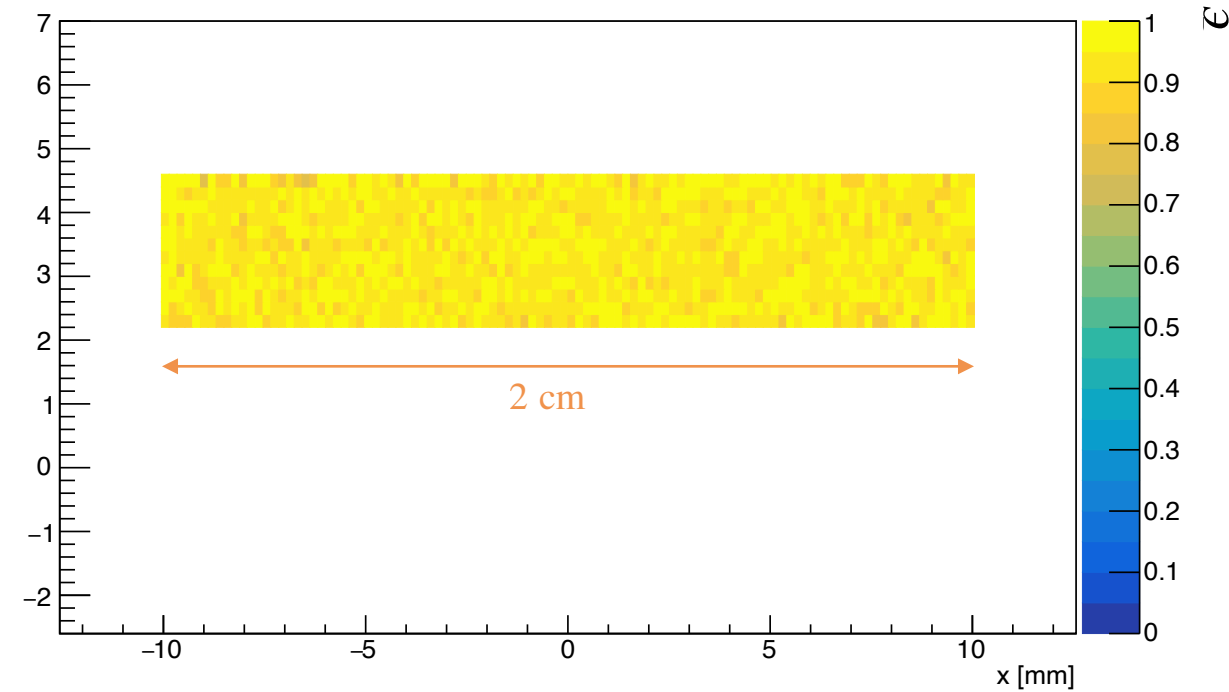
# Global Efficiency

## Efficiency in the bond pad region

NOV21:  
Unirradiated,  
@100V bias, short



Strip length including bond pad region (regular)

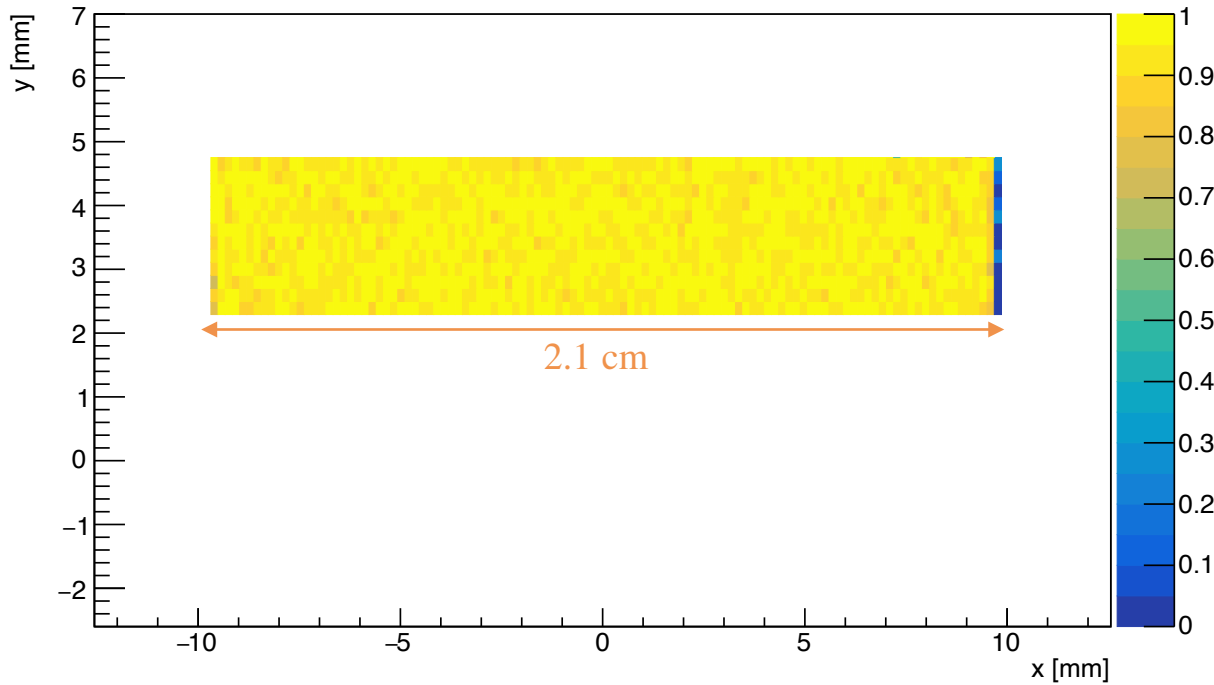


Strip length excluding bond pad region (regular)

# Global Efficiency

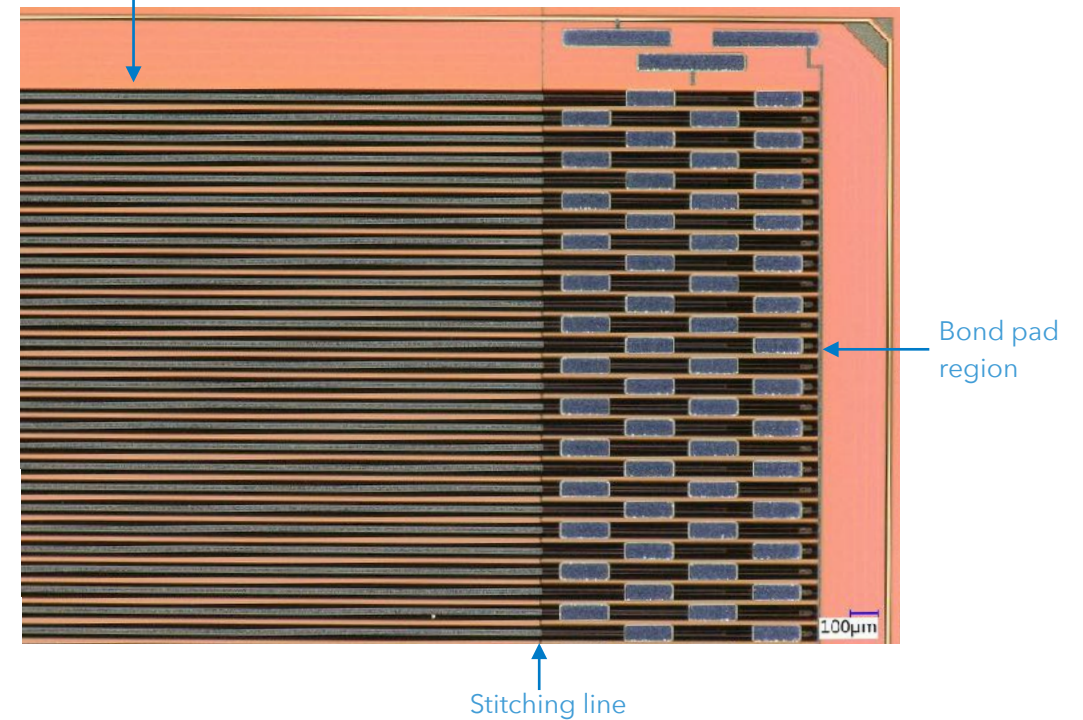
## Efficiency in the bond pad region

Focus on Bond pad region in TB March 23



Strip length including bond pad region (regular)

Regular strip-implant



Microscopic picture of regular strip implants

# Summary & Outlook

## What we have learned and what's next ...

- Stitching does not impact efficiency!
  - Efficiency drop for LD designs and irradiated samples

- Analysis of Mar23 TB campaign to verify results
  - high statistic runs, timing plane, bond pad region
- New sensor submission in discussion



# Backup



# Stitching for Silicon Sensors

## Connection of neighbouring reticles

- Sensor is divided into small(er) parts
- Different reticles used to imprint these parts
- **Reticle B**: is imprinted, moved, imprinted...

Stitching is possible in  
both dimensions!

